

PATENT ABSTRACTS OF JAPAN

(11)Publication number : 02-098126

(43)Date of publication of application : 10.04.1990

(51)Int.Cl. H01L 21/027
G03F 7/16
// B05C 11/08

(21)Application number : 63-249791 (71)Applicant : OKI ELECTRIC IND CO LTD

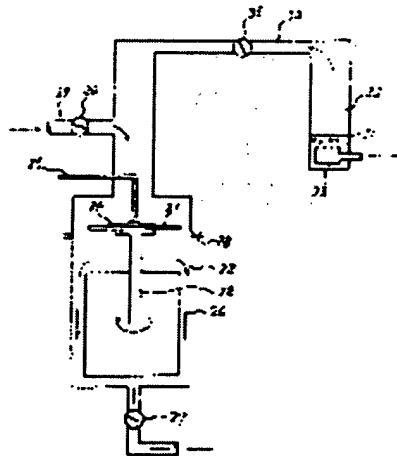
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(54) PHOTO RESIST COATER

(57)Abstract:

PURPOSE: To realize a highly reliable coating by a method wherein a thin film is formed while a spinner chuck is rotated and dampers are opened and shut to separate processes of evaporation and removal of a contained solvent.

CONSTITUTION: Solvent vapor of a photoresist 24 flows into a coating cup 23 through an opening/shutting damper 35 provided at an airpipe 34 and gas containing no solvent vapor flows in the cup 23 through an opening/shutting damper 30 provided at an airpipe 29. Moreover, three exhaust tubes 26 and more are provided at the lower part of the cup 23 and are unified to exhaust the gas to the exterior through an opening/shutting damper 27. First, when the dampers 27 and 30 are shut and the damper 35 is opened, the cup 23 is filled with an atmosphere containing the solvent for the resist 24. Here, the dampers 27 and 35 are operated while a spinner chuck 22 is rotated, the solvent is evaporated and a thin film capable of being executed an exposure treatment is formed. Then, the chuck 22 is stopped, the dampers 27 and 30 are operated and the gas in the cup 23 is removed. Thereby, evaporation and removal processes are separated from each other and a highly reliable coating can be carried out without damaging the uniformity of the thin film.



LEGAL STATUS

[Date of request for examination]

[Date of sending the examiner's decision of rejection]

[Kind of final disposal of application other than the examiner's decision of rejection or application converted registration]

[Date of final disposal for application]

[Patent number]

[Date of registration]

[Number of appeal against examiner's decision of rejection]

[Date of requesting appeal against examiner's decision of rejection]

[Date of extinction of right]

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